

<b>Notice of References Cited</b>	Application/Control No. 09/103,873	Applicant(s)/Patent Under Reexamination NAGANO ET AL.	
	Examiner José R Díaz	Art Unit 2815	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,374,578	12-1994	Patel et al.	438/3
	B	US-5,750,419	05-1998	Zafar, Sufi	438/3
	C	US-5,624,864	04-1997	Arita et al.	438/3
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Fundamentals of Chemical of Chemical Vapor Deposition. TEOS / OZONE Thermal CVD. Film Quality: Moisture, Stress, Cracking. Tutorial [online]. TimeDomain CVD Inc., 2002 [retrieved on 2004-02-18]. Retrieved from the Internet: < URL:
	V	<a href="http://www.timedomaincvd.com/CVD_Fundamentals/films/TEOS_O3_thermal.html">http://www.timedomaincvd.com/CVD_Fundamentals/films/TEOS_O3_thermal.html</a> >
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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